

Antisite pair recombination in SiC by a modified concerted exchange mechanism

related publication:

Posselt, M., Gao, F., Weber, W. J.,

Atomistic simulations on the thermal stability of the antisite pair in 3C- and 4H-SiC,

Phys. Rev. B 73 (2006) 125206

Motivation

D_1 PL center:

- is observed at low temperature PL measurements, after electron, ion, or neutron irradiation, is found in as-grown material and in epitaxial layers, in n and p type material, in $3C$, $4H$, $6H$ and $15R$ polytypes
- is found to be stable after thermal treatment to above 2000 K

D_1 (zero phonon) lines

$3C$: $L_1 = 1.972$ eV

$4H$: $L_1 = 2.901$ eV

$6H$: $L_1 = 2.625$ eV, $L_2 = 2.600$ eV, $L_3 = 2.570$ eV

band gap

$3C$: 2.36 eV

$4H$: 3.23 eV

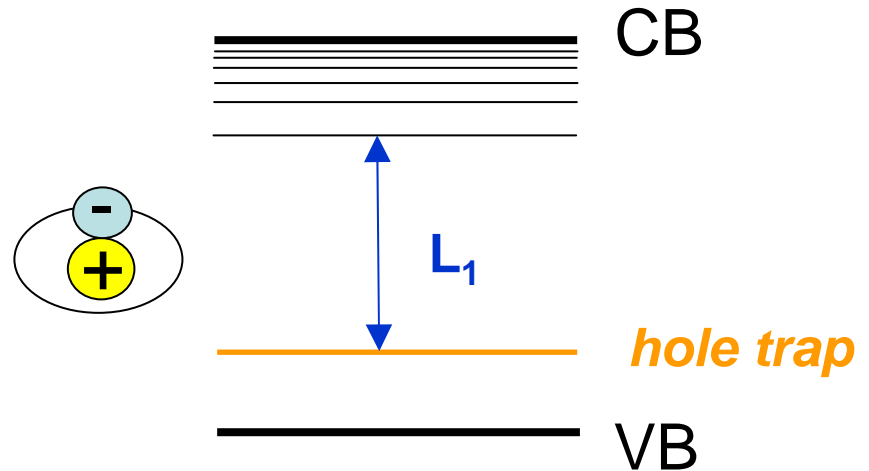
$6H$: 3.00 eV

interpretation

Egilsson et al. 1999/2001 (4H-SiC):

pseudo-donor model

exciton bound
to a **native defect**



- *native defect acts as a hole trap*
- *strongly localized hole captures an electron*
- *bound exciton is formed*
- *recombination between hole and electron gives the L_1 emission line*

candidates for the native defect:

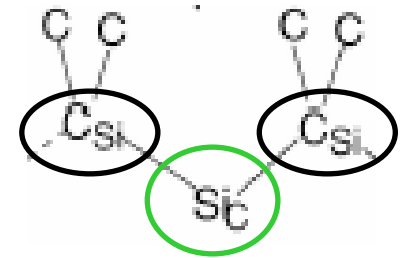
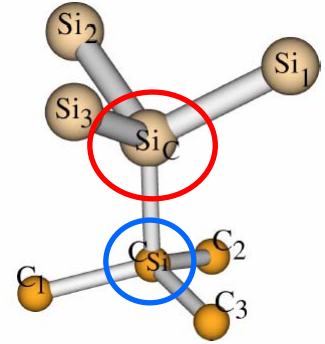
Eberlein et al. 2002:

first-neighbor antisite pair $\text{Si}_C\text{C}_{\text{Si}}$

Gali et al. 2003:

Pinheiro, Rauls et al. 2004/2005:

$\text{Si}_C(\text{C}_{\text{Si}})_2$ complex



however:

calculation of spectra is based on the existence of $\text{Si}_C\text{C}_{\text{Si}}$ and $\text{Si}_C(\text{C}_{\text{Si}})_2$, their thermal stability has not yet been checked

this work: dynamic simulations on the thermal stability of $\text{Si}_C\text{C}_{\text{Si}}$ in 3C- and 4H-SiC

Simulation method

systematic classical MD simulations

- interatomic potential of Gao et al.
- supercell with 1152 (3C-SiC) or 1920 (4H-SiC) atoms

ab-initio MD simulations for selected examples

- DFT-code NWCHEM
- supercell with 128 atoms (3C-SiC)

determination of the thermal stability of $Si_C C_{Si}$:

- system with $Si_C C_{Si}$ is heated rapidly to a given temperature
- lifetime of $Si_C C_{Si}$ and the atomic recombination mechanism are analyzed by different independent methods
- due to the statistical nature of the recombination process, several statistically independent simulations must be performed at each temperature

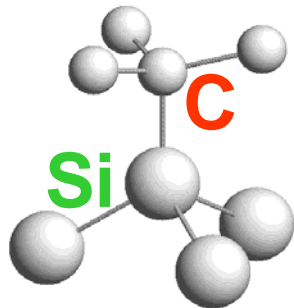
accuracy of the interatomic potential of Gao et al:

V and I formation energies and migration barriers agree reasonably well with results of ab-initio calculations

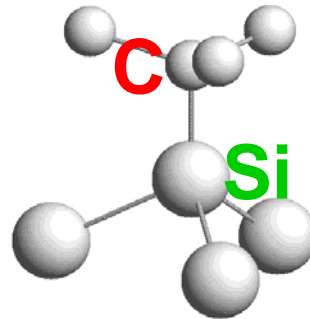
structure and energetics of the antisite pair are also in good agreement with data obtained by ab-initio methods

antisite pair configurations in 3C- and 4H-SiC

3C-SiC

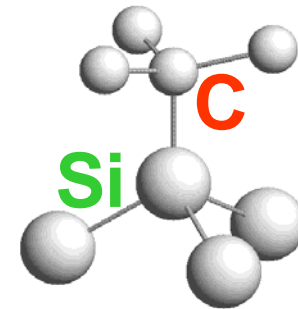


C and Si on hexagonal sites (1)



4H-SiC

C and Si on cubic sites (1),
mixed configuration (2)



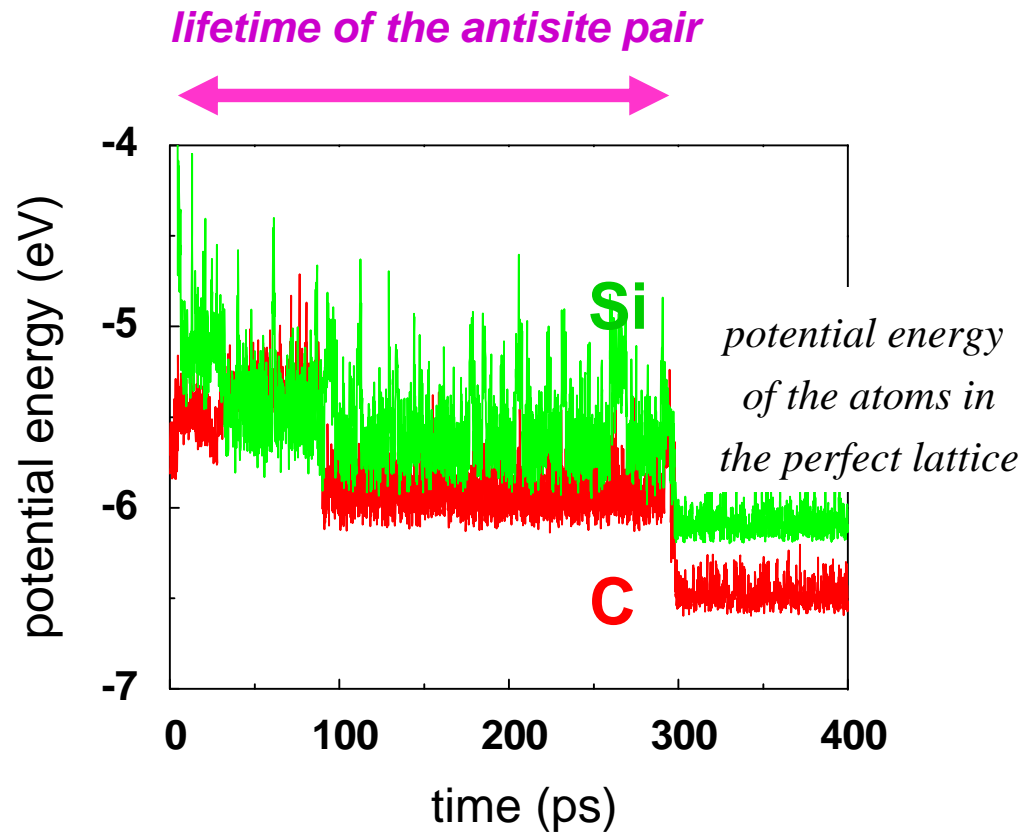
Reference	CP			SCC-DFTB	DF					
	this work			Rauls <i>et al.</i> 2001	Wang <i>et al.</i> 1988	Torpo <i>et al.</i> 1999	Eberlein <i>et al.</i> 2002		Gali <i>et al.</i> 2003	Gali <i>et al.</i> 2003
	3C-SiC	4H-SiC, atoms on two hexagonal sites	4H-SiC, other configurations	4H-SiC, c, atoms on two cubic sites	3C-SiC	3C-SiC	4H-SiC, c	4H-SiC, not c	3C-SiC	4H-SiC
formation energy (eV)	6.65	6.72	6.66	5.2	5.9	5.8	5.68	5.33	6.1	5.9
binding energy (eV)	2.82	2.75	2.83	2.5	2.5	2.49	2.07	2.42		
Si-C bond length	-3%	-4%	-3%	-2%		-2%				
C-C bond length	-10%	-10%	-10%	-12%		-12%				
Si-Si bond length	+24%	+27%	+24%	+15%		+16%				

Results for 3C-SiC

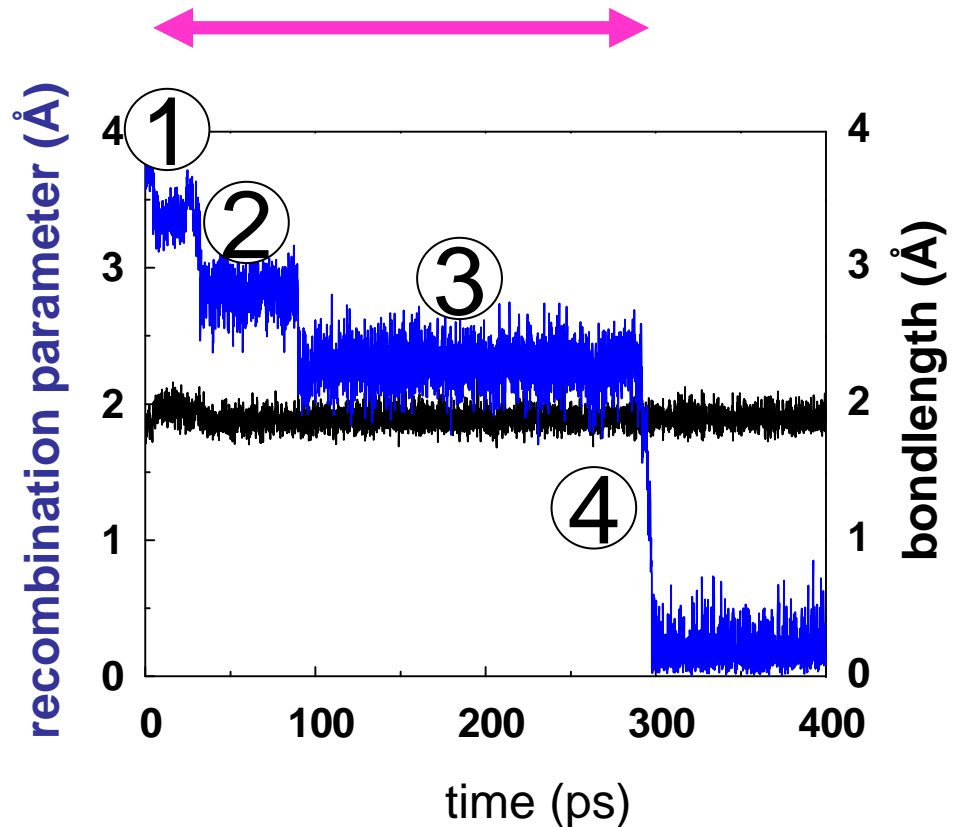
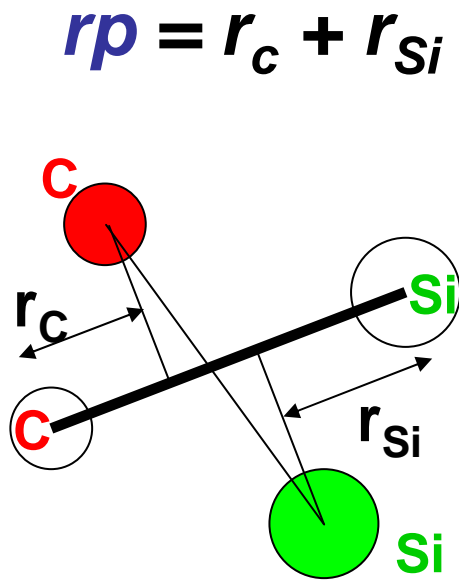
The antisite pair recombination was studied at eleven temperatures between 800 and 2500 K (10 statistically independent simulations at each temperature).

example: $T = 1000$ K

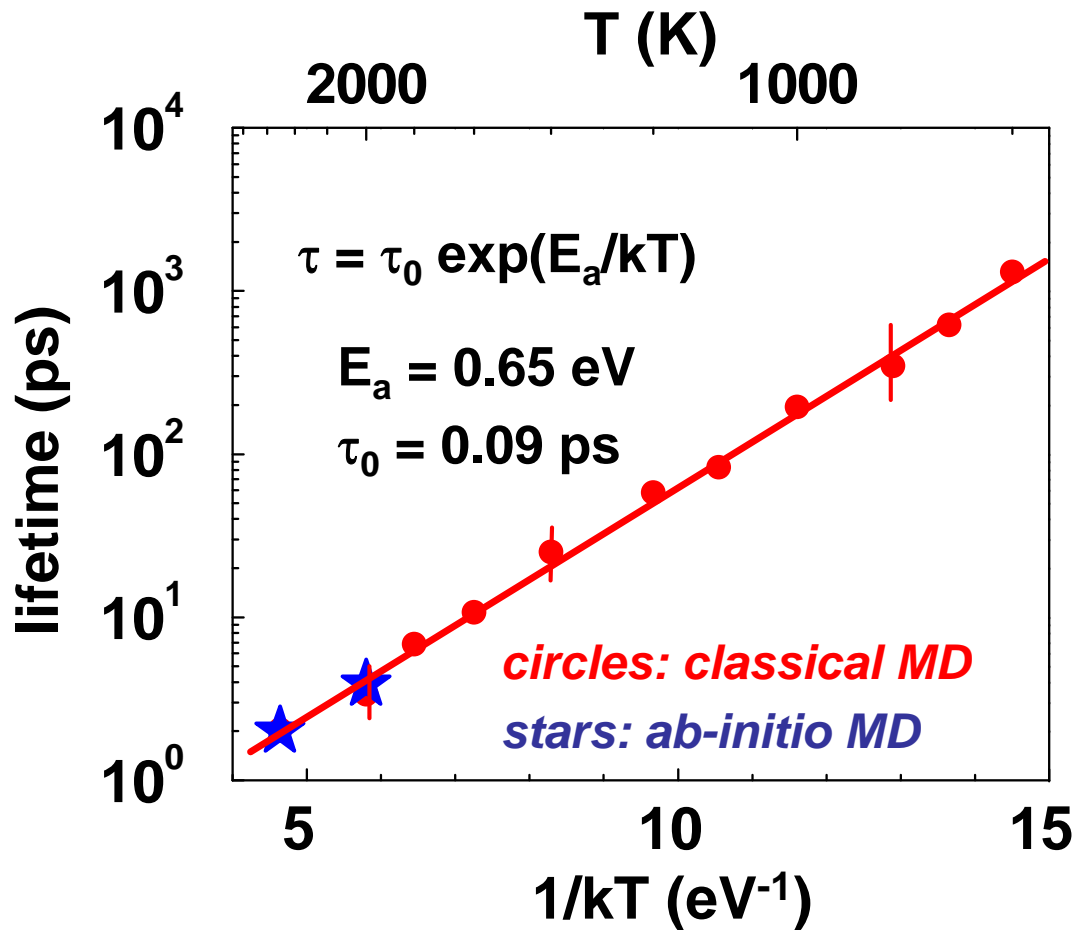
**evolution of
the potential energy
of the two atoms of
the antisite pair**



time dependence of the recombination parameter (rp) and evolution of the bond length between the atoms of the antisite pair



antisite pair recombination consists of 4 stages



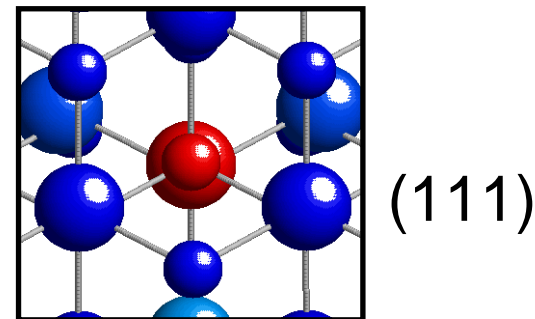
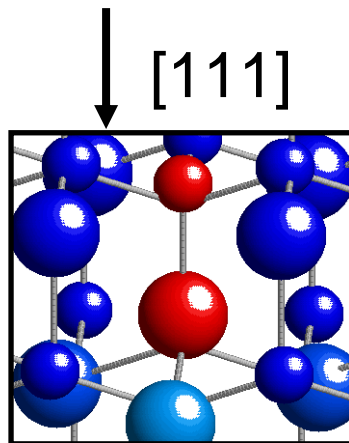
In 3C-SiC the thermal stability of the antisite pair is low. It can be therefore not correlated with the D₁ PL center that is stable up to 2000 K.

modified concerted exchange mechanism

*found by the visualization
of the MD data*

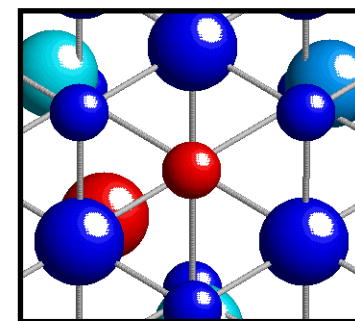
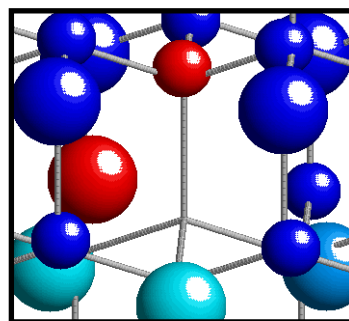
antisite pair

near
(-1-12)



1

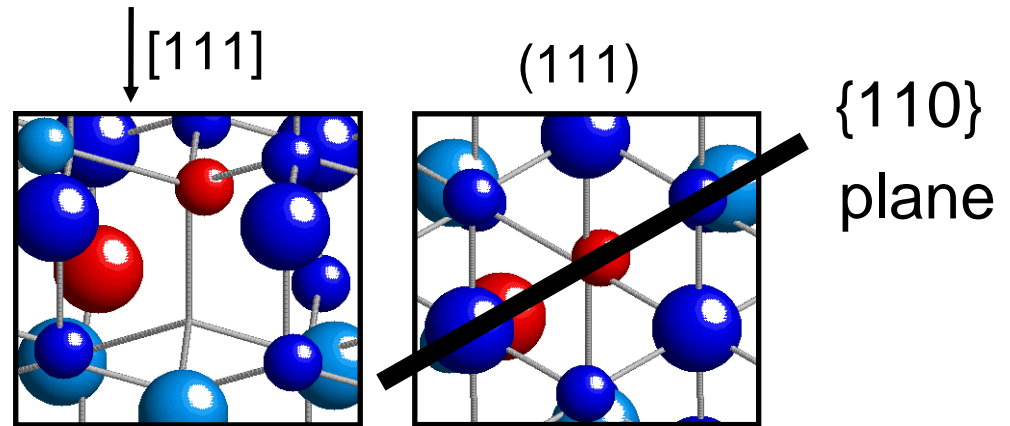
*Si moves to a position
close to a tetrahedral site*





2

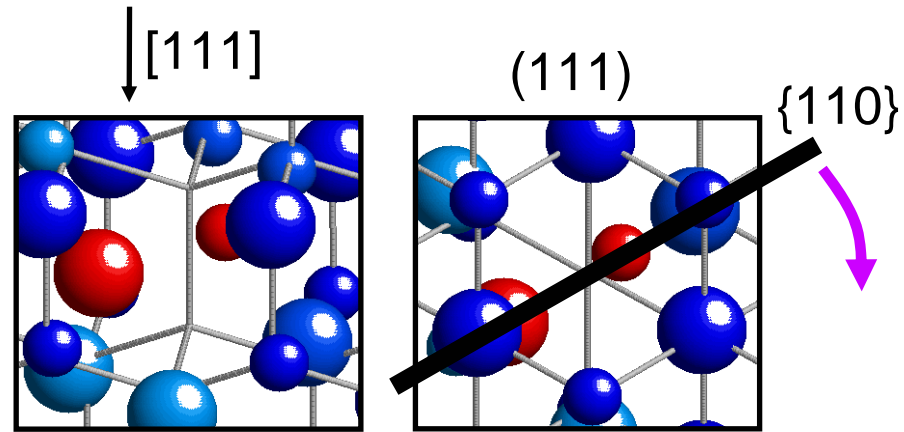
*configuration
changes slightly,
but remains
in a {110} plane*





3

rotation of the Si - C pair in the {110} plane

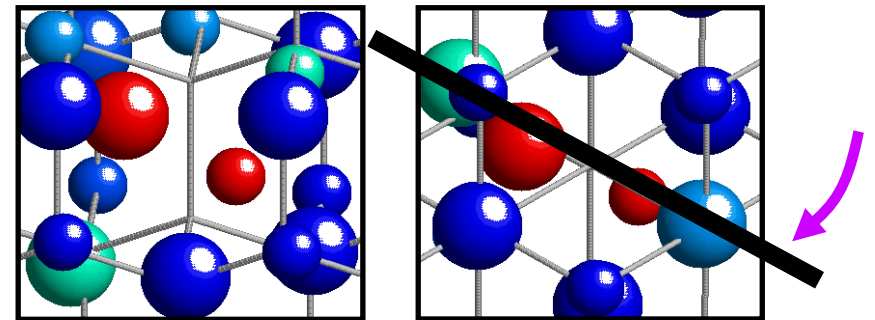


bond defect, type 1



4

further rotation of the Si - C pair, gradual change of the rotation plane until another {110} plane is reached

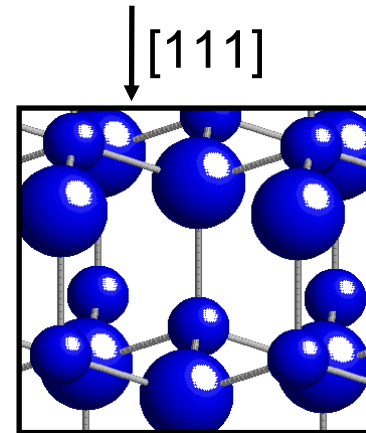


bond defect, type 2

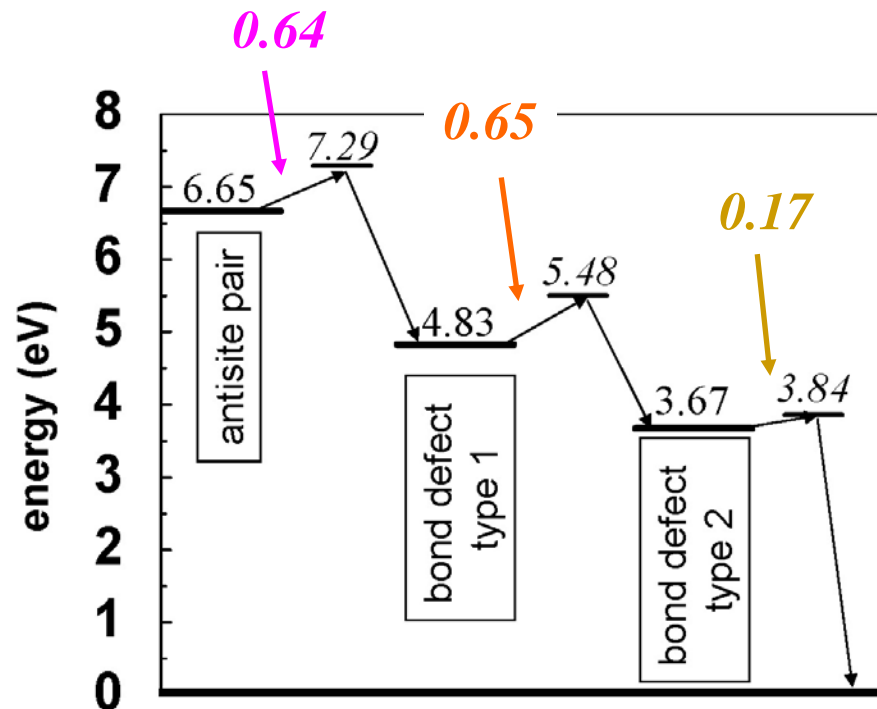


*rotation of the Si-C
pair in the new {110} plane*

perfect lattice

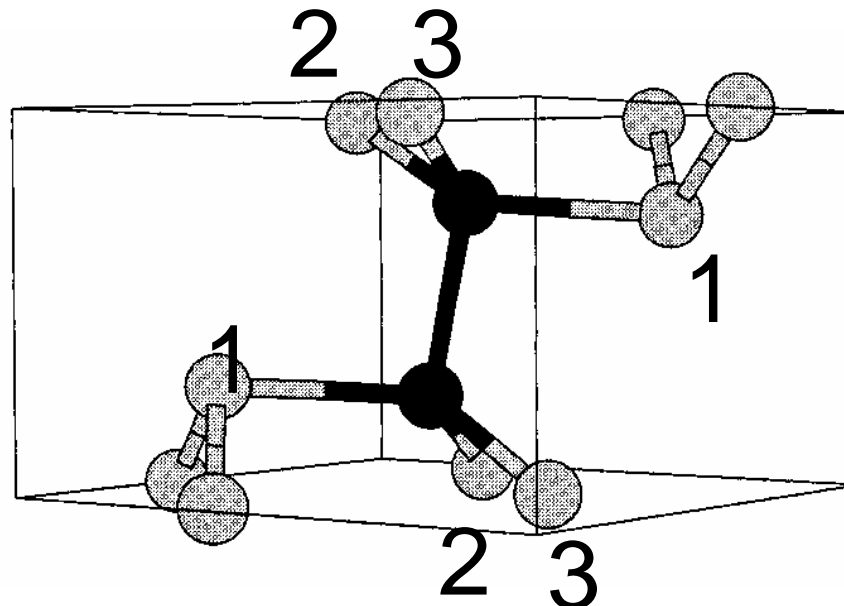


*energetics of the modified
concerted exchange*



bond defect in Si

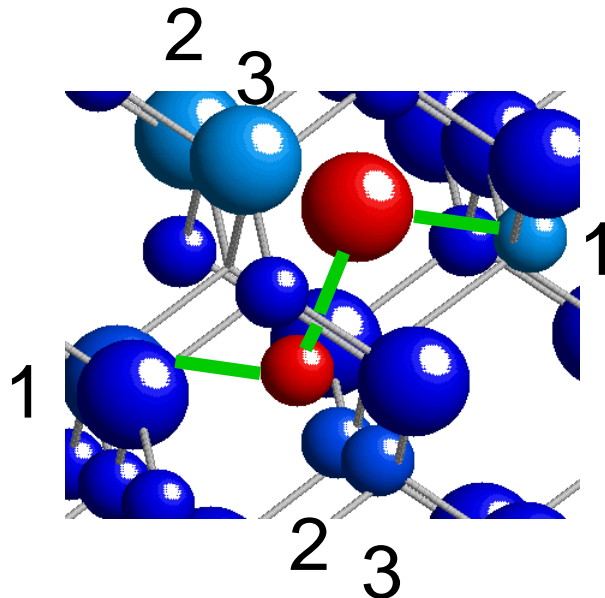
Tang et al. 1997 **result of incomplete
V-I recombination**



all atoms are fourfold coordinated

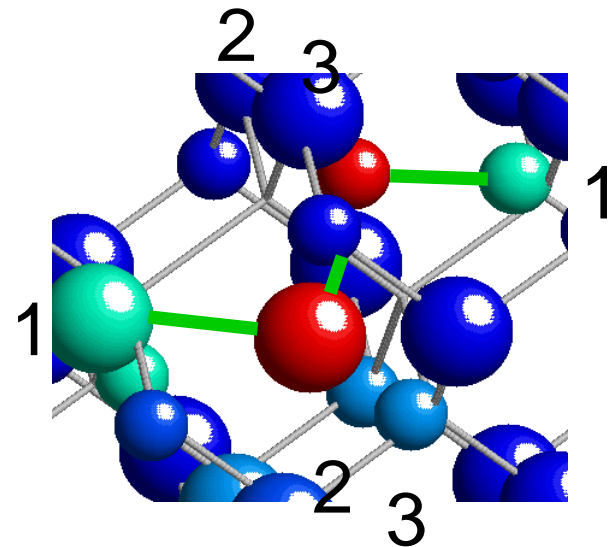
bond defects in 3C-SiC

bond defect,
type 1



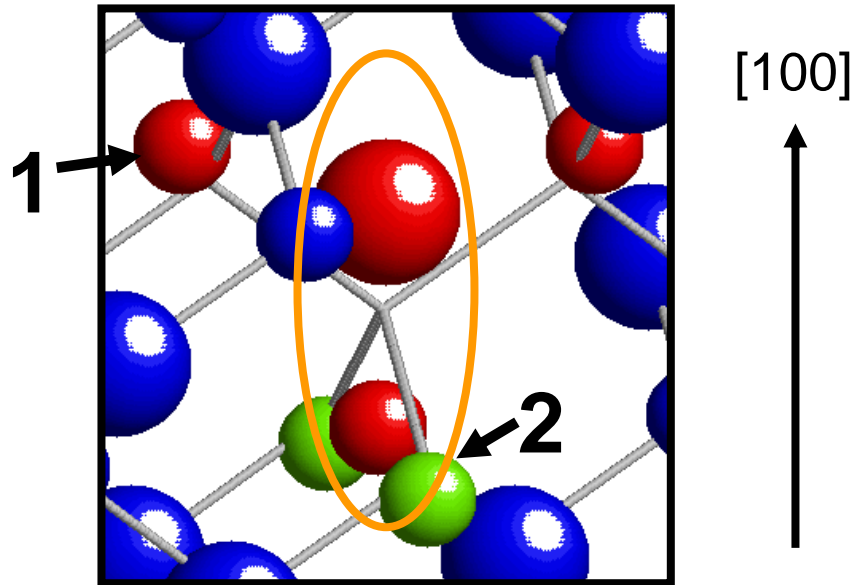
coordination of atoms: ~ 4
nearest neighbors of Si: **2 x Si, 2 x C**
nearest neighbors of C: **2 x Si, 2 x C**

bond defect
type 2



coordination of atoms: ~ 4
nearest neighbors of Si: **1 x Si, 3 x C**
nearest neighbors of C: **3 x Si, 1 x C**

$\langle 100 \rangle \text{C+Si}$
dumbbell

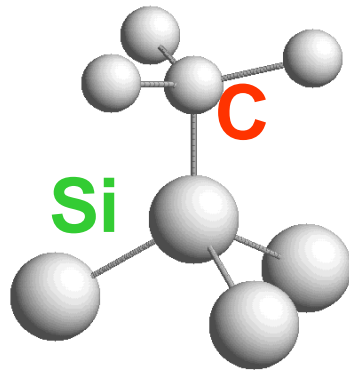


*Similarly to Si, the two bond defects in SiC can be considered as the result of incomplete recombination of V_C and $\langle 100 \rangle \text{C+Si}$.
This process is therefore one of the possible pathways for antisite pair formation.*

Results for 4H-SiC

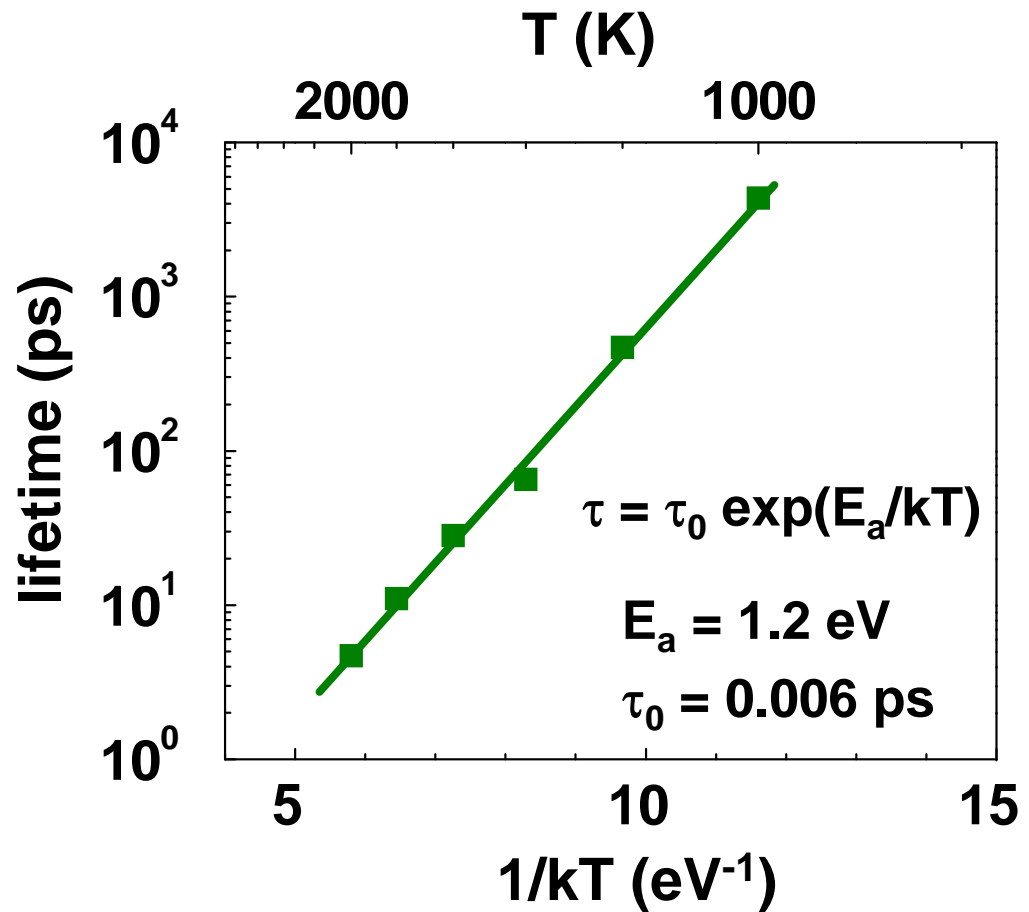
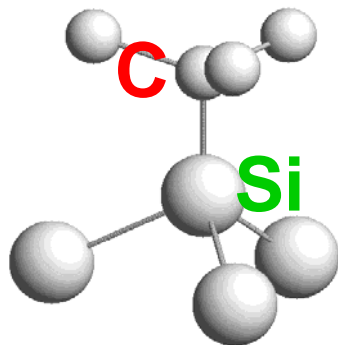
The antisite pair recombination was studied at nine temperatures between 900 and 2000 K.

C and Si on cubic sites (1),
mixed configuration (2)



results are almost identical
to those for 3C-SiC

C and Si on hexagonal sites (1)



The lifetime of the antisite pair with atoms on hexagonal sites is different to that of the three other types of antisite pairs.

The recombination mechanism is not a concerted exchange. It is rather characterized by the separate motion of the atoms.

Two reaction paths were identified:

- (i) main path: only the two atoms of the antisite pair move significantly.***
- (ii) other path: motion of more than two atoms.***

In 4H-SiC the thermal stability of the four types of antisite pairs is low. They can be therefore not correlated with the D₁ PL center that is stable up to 2000 K.

Summary

- The thermal stability of the antisite pair in *3C*- and *4H-SiC* is low. Therefore, it is not a candidate for the D_1 PL center.
- The recombination of the antisite pair in *3C-SiC* and of three antisite pair configurations in *4H-SiC* occur via a modified concerted exchange, with two types of bond defects as intermediate states.